

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants: Hwang et al.

Examiner: Rosasco, Stephen D

Serial No: 10/827,556

Group Art Unit: 1756

Filed: April 19, 2004

Docket: 8028-43 (SPX200304-0016US)

**FOR: PHOTOMASK FOR FORMING PHOTORESIST PATTERNS  
REPEATING IN TWO DIMENSIONS AND METHOD OF FABRICATING THE  
SAME**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**AMENDMENT IN RESPONSE TO FINAL OFFICE ACTION**

Sir:

This Amendment is submitted in response to the October 4, 2007 Office Action issued by the United States Patent and Trademark Office in connection with the above-identified application.